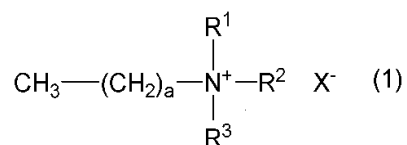


ABSTRACT

Provided is a treatment liquid for a semiconductor wafer or the like used in a process for forming a semiconductor. Namely a treatment liquid containing (A) a hypochlorite ion, and (B) an alkylammonium salt expressed by the following Formula (1), or the like is provided.



(In the Formula, “a” is an integer from 6 to 20; R¹, R², and R³ are independently, for example, an alkyl group with a carbon number from 1 to 20; and X⁻ is, for example, a chloride ion.)

[No Figure]